

## SUPPORTING INFORMATION

# Molecularly modified ultrathin Al<sub>2</sub>O<sub>3</sub> layers: proton-conductive, oxygen-impermeable nanomembranes for catalytic surfaces

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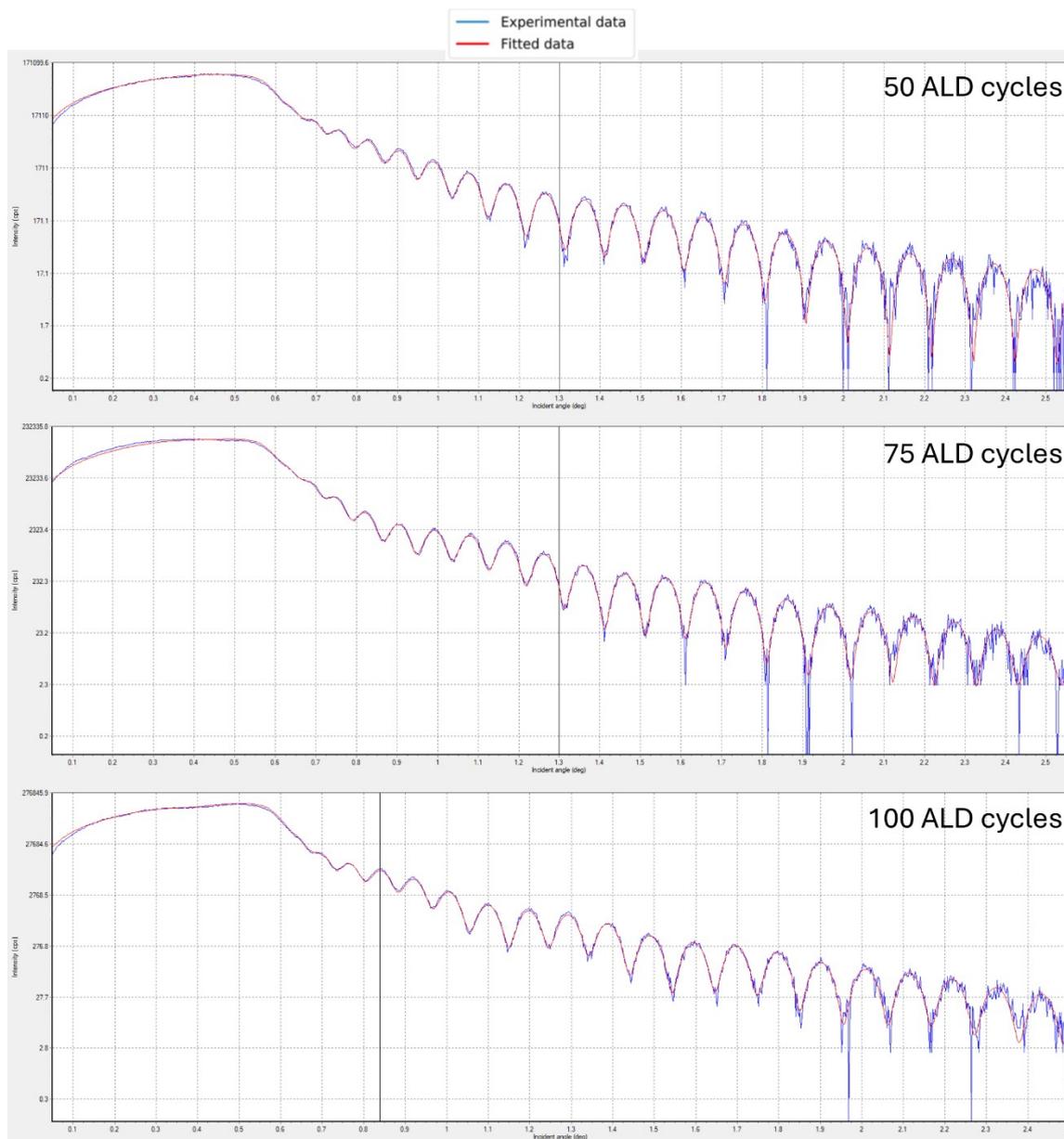


Figure S1: X-ray reflectivity (XRR) experimental data and corresponding fitted models for alumina films deposited by atomic layer deposition using trimethylaluminum and water for 50, 75, and 100 cycles. The fits were used to extract film thickness as shown in Figure S3. Measurements were performed using a Cu K $\alpha$  radiation source ( $\lambda = 1.5406 \text{ \AA}$ ). Experimental data were fitted using a multilayer slab model

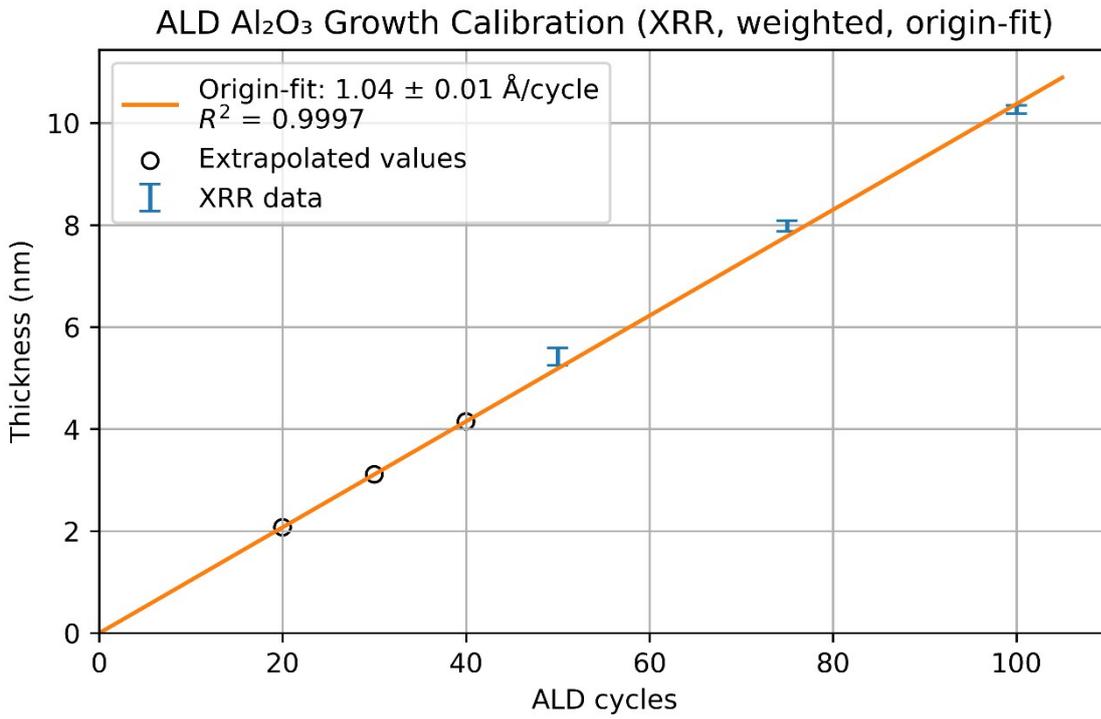


Figure S2: Growth calibration curve for atomic layer deposition of alumina using the XRR data in Figure S2.

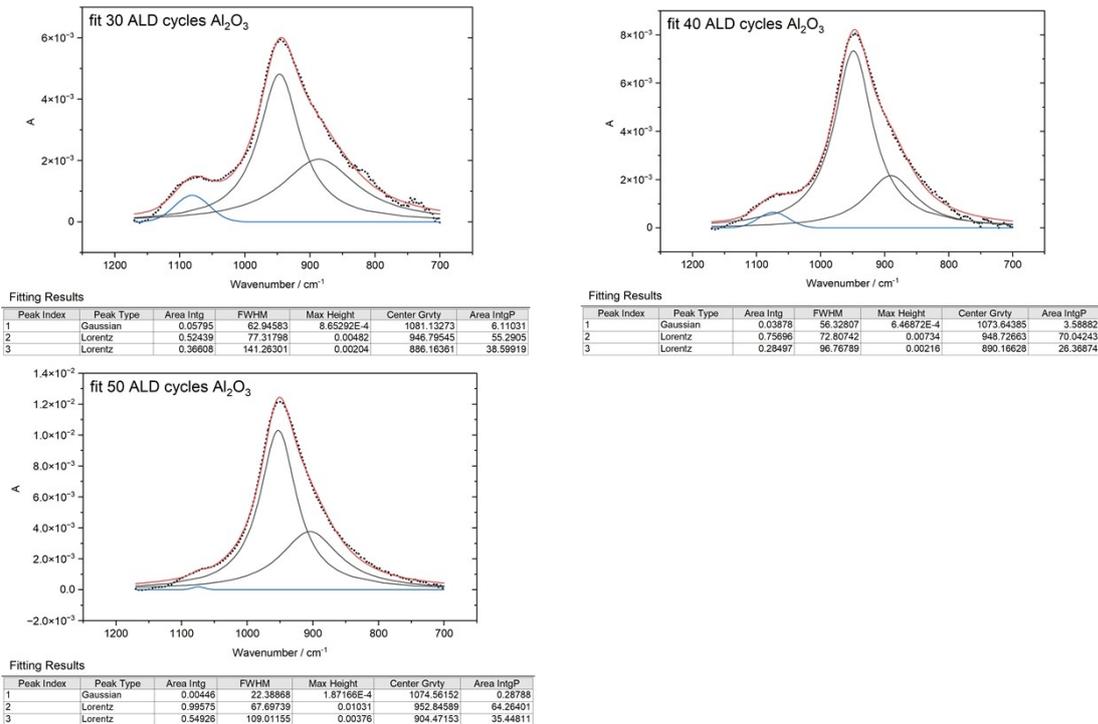


Figure S3: FT-IRRA spectra (dotted black line) with cumulative fit (red line), showing alumina-related contributions (grey Lorentzian components) and the aluminum hydroxide band (blue Gaussian component) for 30 (top left), 40 (top right), and 50 (bottom left) ALD cycles.

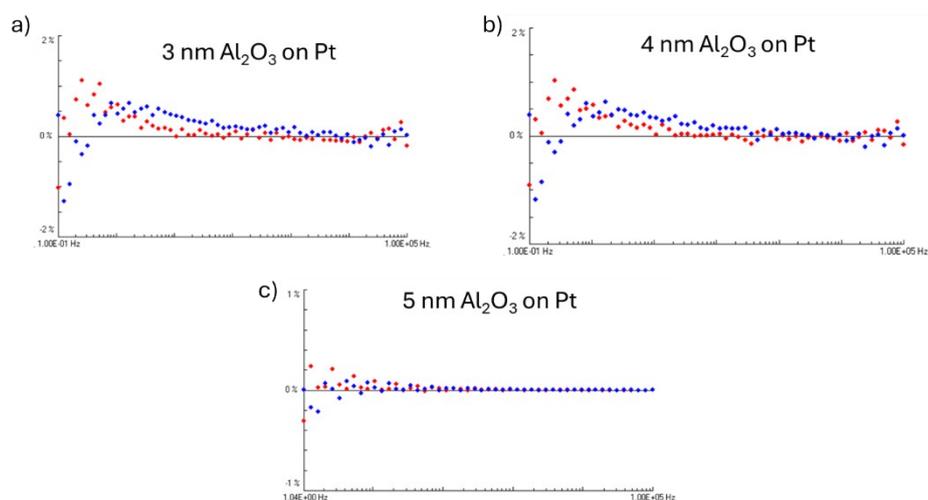


Figure S4: Kramers-Kronig test of the EIS data in Figure 2a.

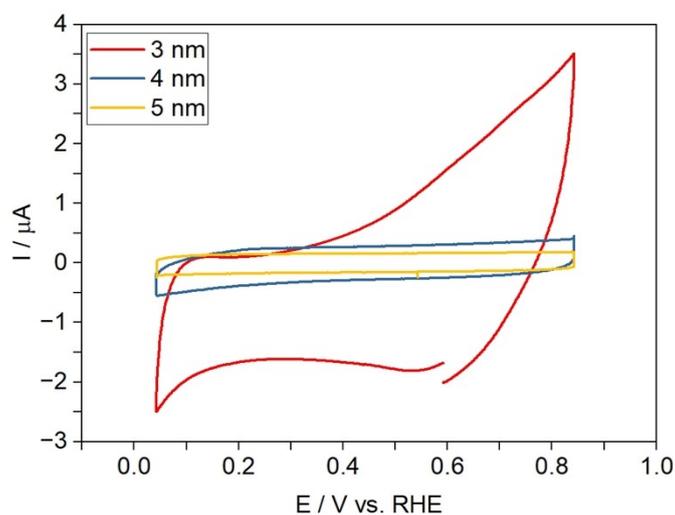


Figure S5: Cyclic voltammograms at  $100 \text{ mV s}^{-1}$  of Pt electrodes coated with 3, 4, and 5 nm alumina layers. The 3 nm sample was tested in ferro/ferricyanide solution to demonstrate its blocking behavior toward larger redox ions. These results are consistent with the EIS analysis, showing only a modest reduction in the electrical double-layer capacitance with increasing alumina thickness.

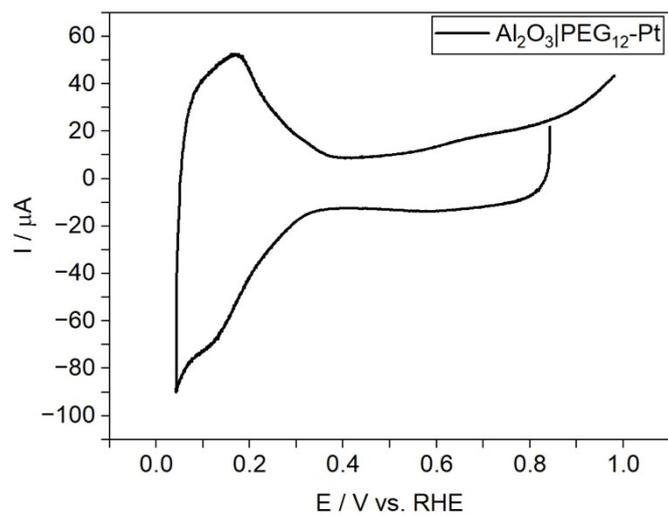


Figure S6: CV of 3 nm Al<sub>2</sub>O<sub>3</sub>|PEG<sub>10</sub>-Pt after 10 cycles in 0.5 M Na<sub>2</sub>SO<sub>4</sub> (pH 4), showing the significantly increased H<sub>upd</sub> currents. The potential window was limited to below 0.9 V vs RHE to avoid anodic oxidation of the underlying Pt electrode, which could otherwise alter or rupture the alumina layer.

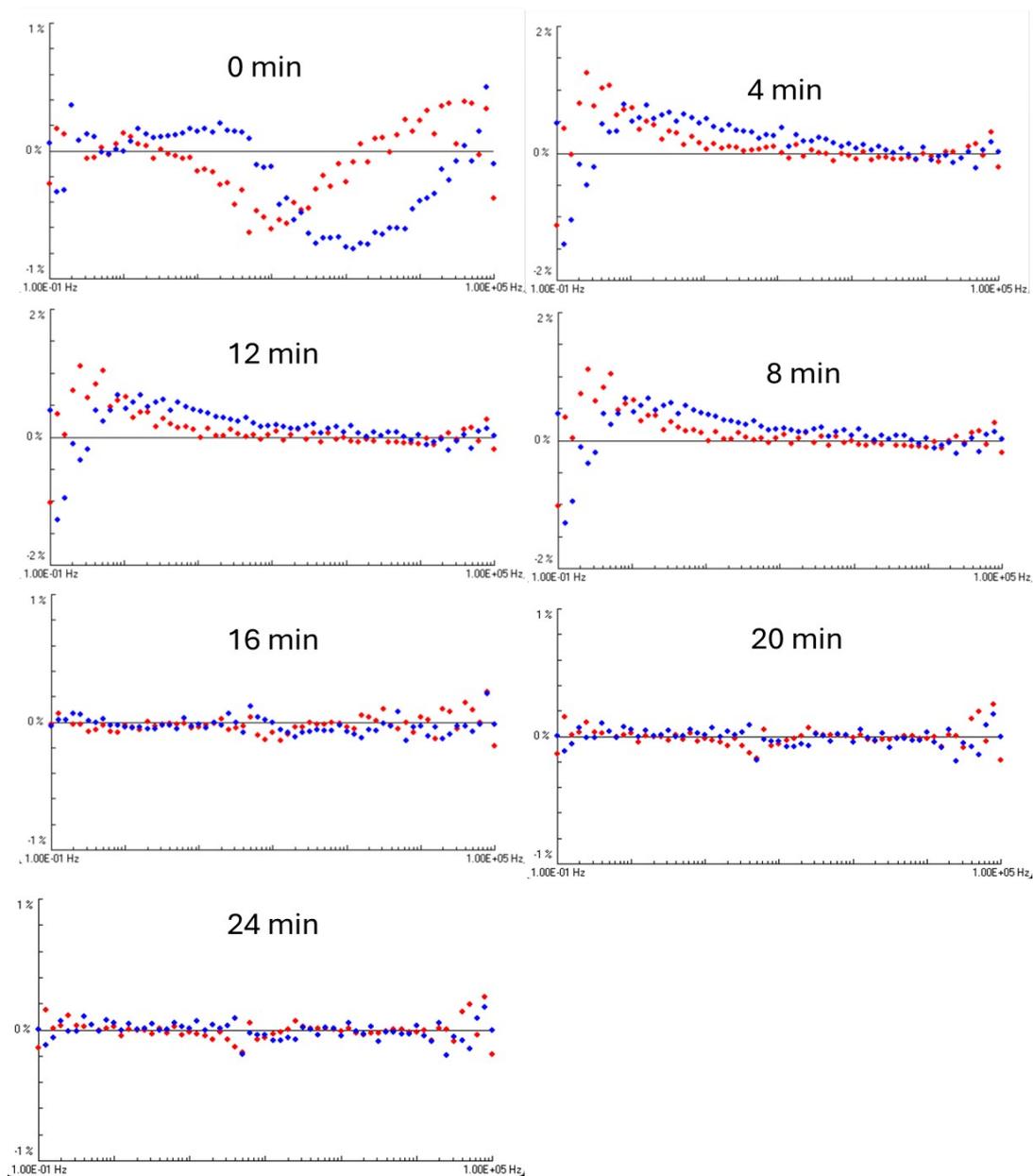


Figure S7: Kramers-Kronig tests for 3 nm Al<sub>2</sub>O<sub>3</sub>|PEG<sub>12</sub>-Pt. The first KK test shows that the EIS data is far out of equilibrium.

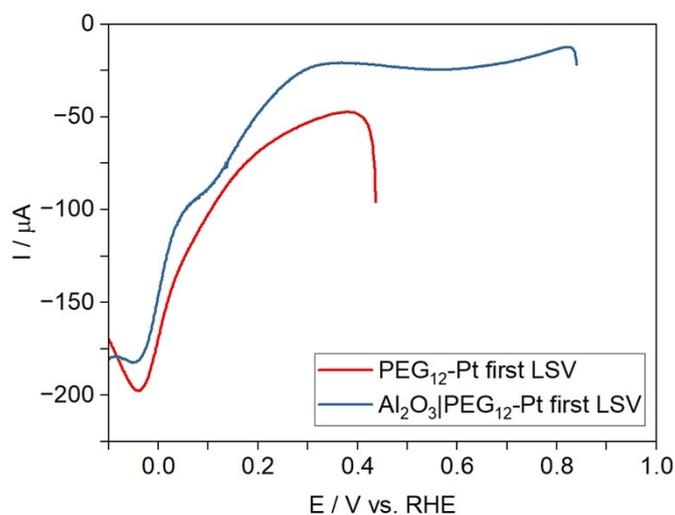


Figure S8: First linear sweep voltammogram starting from open circuit potential of 3 nm  $\text{Al}_2\text{O}_3|\text{PEG}_{10}\text{-Pt}$  and  $\text{PEG}_{10}\text{-Pt}$  in 0.5 M  $\text{Na}_2\text{SO}_4$  (pH 4), highlighting the  $H_{\text{upd}}$  currents, into which the thiol stripping current is convoluted.

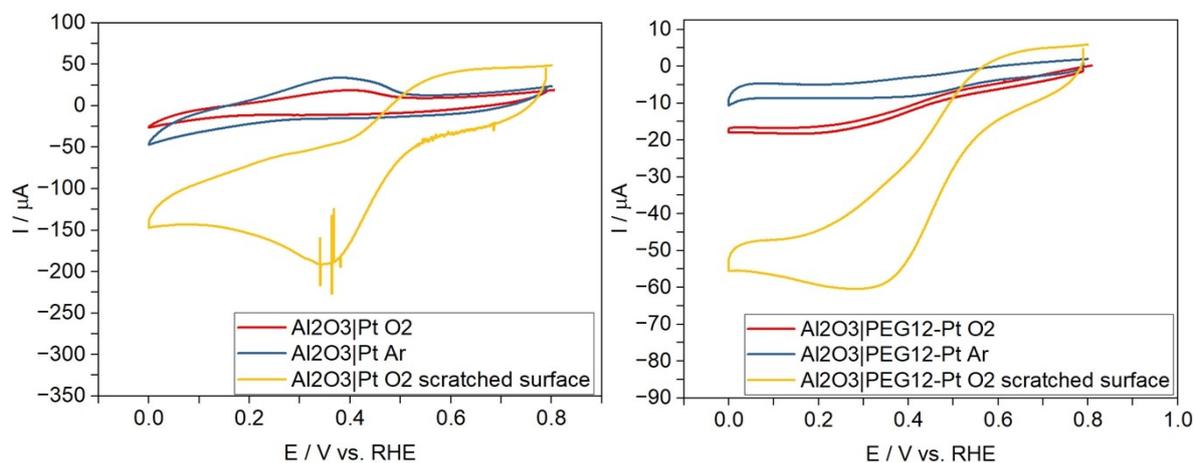


Figure S9: 10<sup>th</sup> CV of 3 nm  $\text{Al}_2\text{O}_3|\text{Pt}$  (left) and  $\text{Al}_2\text{O}_3|\text{PEG}_{12}\text{-Pt}$  (right) in  $\text{O}_2$ , Ar, and after scratching the surface in  $\text{O}_2$ .